

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE



in re Application of

Tuqiang NI et al

Serial No. 09/689,616

Filed: October 13, 2000

For: VACUUM PLASMA PROCESSOR HAVING A CHAMBER WITH ELECTRODES
AND A COIL FOR PLASMA EXCITATION AND METHOD OF OPERATING
SAMEAMENDMENTAssistant Commissioner for Patents
Washington, D. C. 20231

Sir:

In response to the June 27, 2002 Office Action, please amend
the application as follows:

IN THE CLAIMS:

Please amend claims 7, 8, 29, 30 and 31 as follows:

7. (amended) The vacuum plasma processor of claim 3 wherein
the dielectric window, semiconductor member and non-magnetic metal
arrangement are in a roof structure of the chamber, the chamber
having a center portion, the coil having an interior portion that
is spaced from the chamber center portion so peripheral portions of
the semiconductor member are not outside the coil interior portion,
the non-magnetic metal arrangement having peripheral portions
spaced from the chamber center portion by approximately the same

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